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STATEMENT BY APPLICANT Filed: November 29, 2007

INFORMATION DISCLOSURE

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Sheet 1 of 3

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Application Number	Unassigned		
Filing Date			
First Named Inventor	Igor BARGATIN et al.		
Group Art Unit	Unassigned		
Examiner Name	Unassigned		
Attorney Docket Number	049411-0340		

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Examiner Initials*	Cite No.1	U.S. Patent D Number	Code <sup>2</sup> (if	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
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Sheet 2 of

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Application Number	Unassigned	
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Sheet 3 of 3

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	,	NON PATENT LITERATURE DOCUMENTS	
Examiner nitials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.	
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